20637403 2PCT
OBLON ET AL (703) 413-3000
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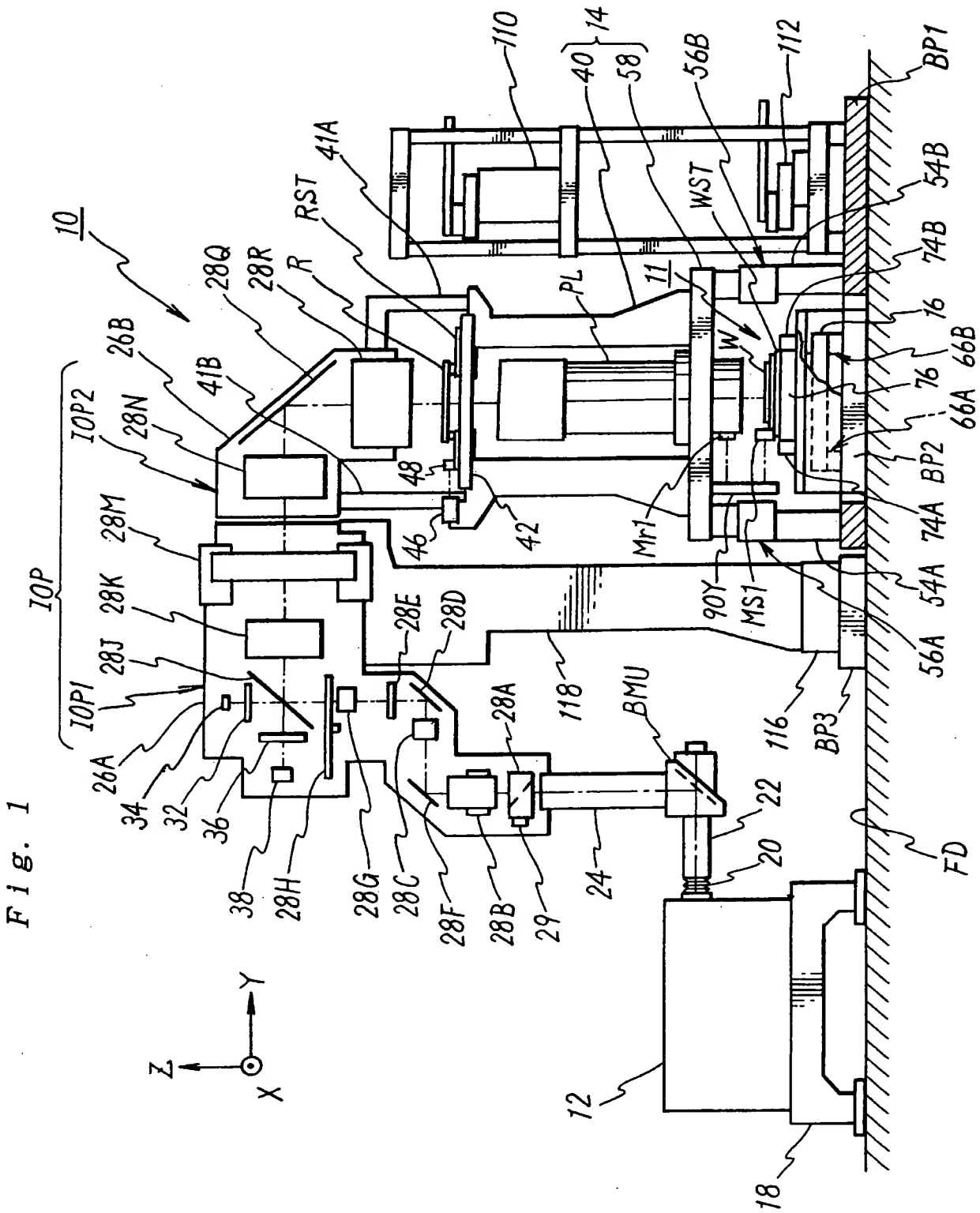


Fig. 1

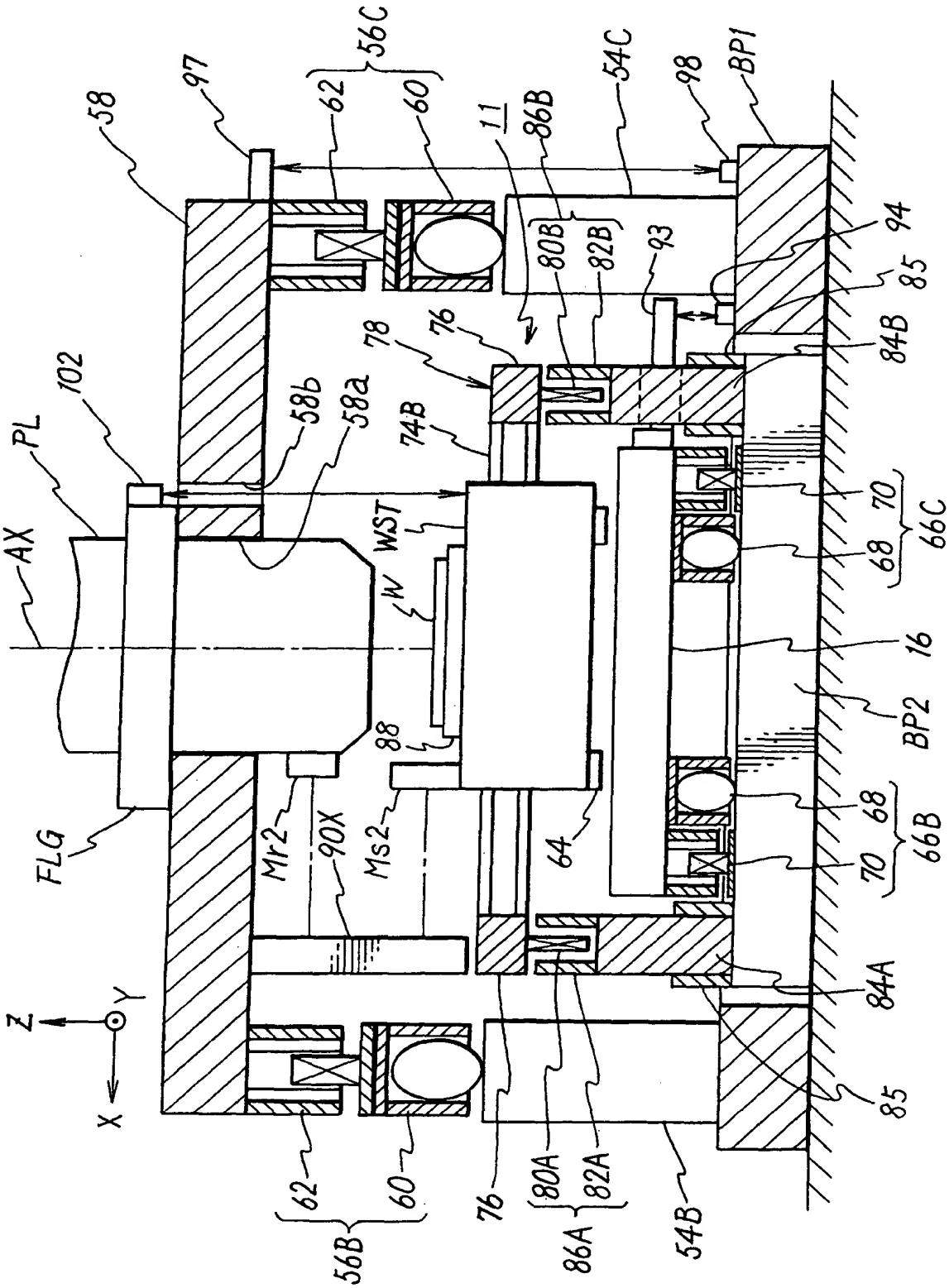

58
97
62
56C
60
11
86B
54C
98
BP1
80B
82B
93
94
85
84B
78
76
102
PL
58b
58a
74B
AX
WST
W
70
68
66C
16
BP2
88
FLG
Mr2
90X
Ms2
64
66B
84A
Z
Y
X
62
60
56B
76
80A
82A
86A
54B

Fig. 2

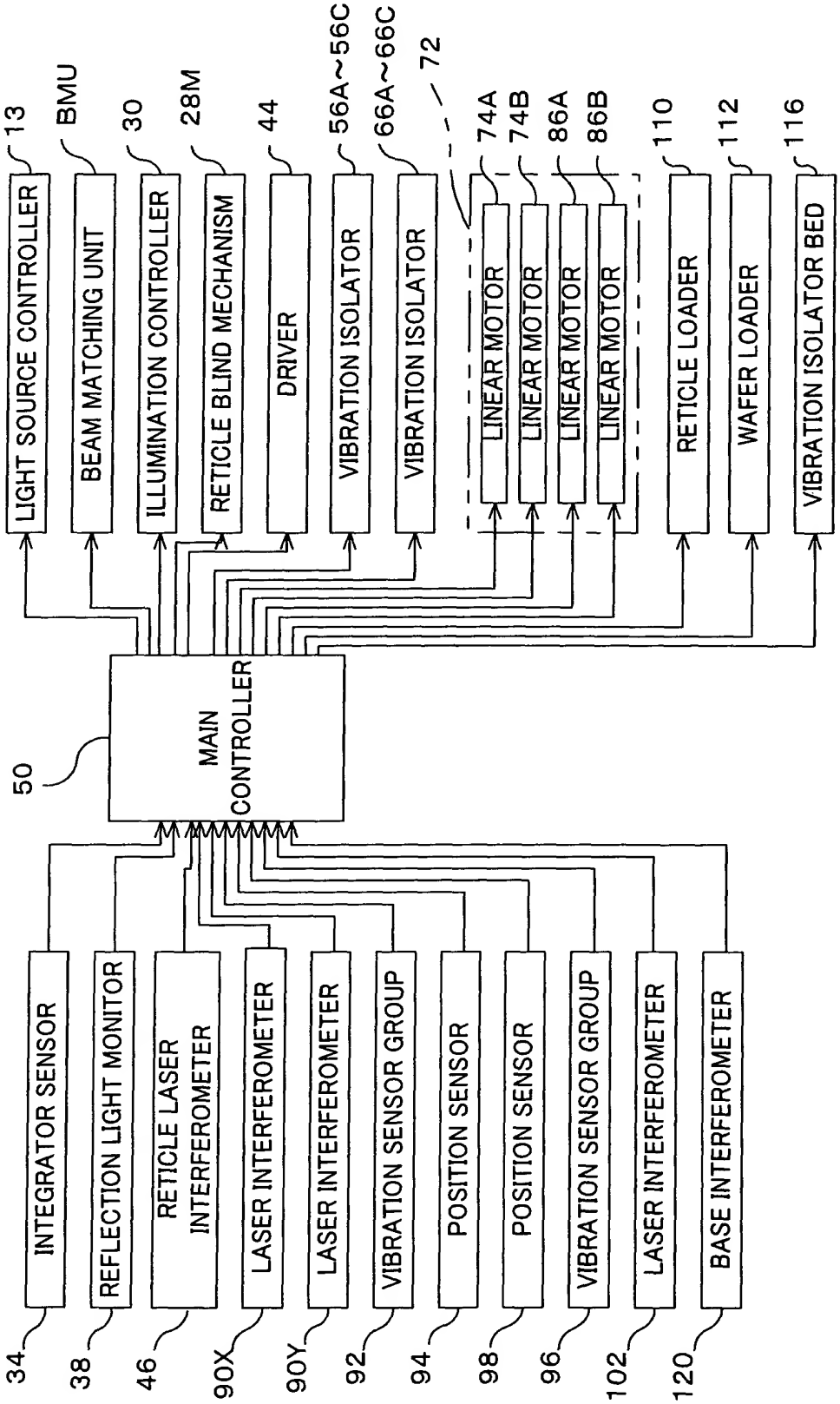
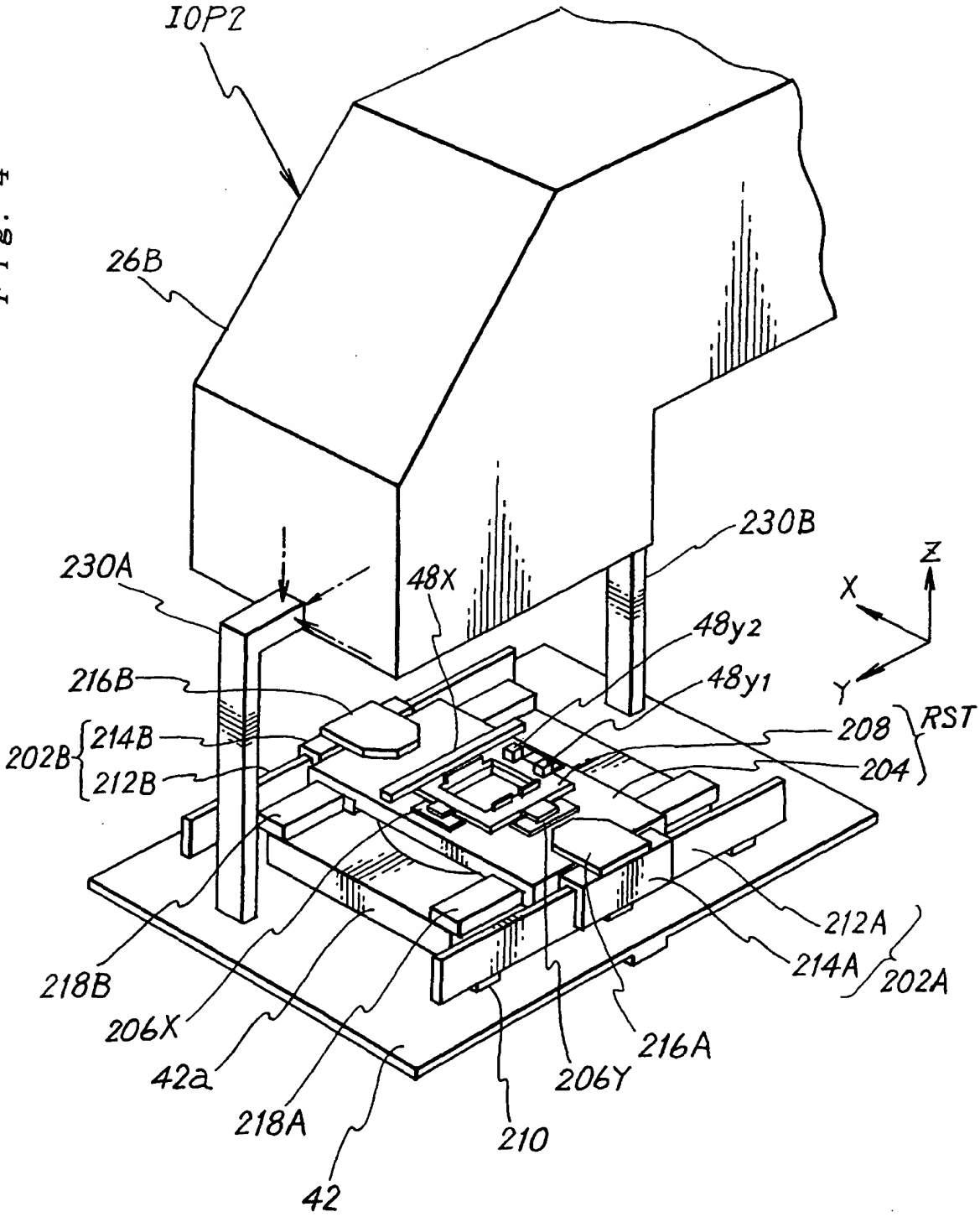

LIGHT SOURCE CONTROLLER
13
BEAM MATCHING UNIT
BMU
ILLUMINATION CONTROLLER
30
RETICLE BLIND MECHANISM
28M
DRIVER
44
VIBRATION ISOLATOR
56A~56C
VIBRATION ISOLATOR
66A~66C
72
LINEAR MOTOR
74A
LINEAR MOTOR
74B
LINEAR MOTOR
86A
LINEAR MOTOR
86B
RETICLE LOADER
110
WAFER LOADER
112
VIBRATION ISOLATOR BED
116
MAIN CONTROLLER
50
INTEGRATOR SENSOR
34
REFLECTION LIGHT MONITOR
38
RETICLE LASER INTERFEROMETER
46
LASER INTERFEROMETER
90X
LASER INTERFEROMETER
90Y
VIBRATION SENSOR GROUP
92
POSITION SENSOR
94
POSITION SENSOR
98
VIBRATION SENSOR GROUP
96
LASER INTERFEROMETER
102
BASE INTERFEROMETER
120

Fig. 3

Fig. 4


IOP2
26B
230A
48X
230B
Z
X
Y
48y2
48y1
216B
208
RST
202B
214B
212B
204
212A
214A
202A
218B
206X
42a
218A
42
210
206Y
216A

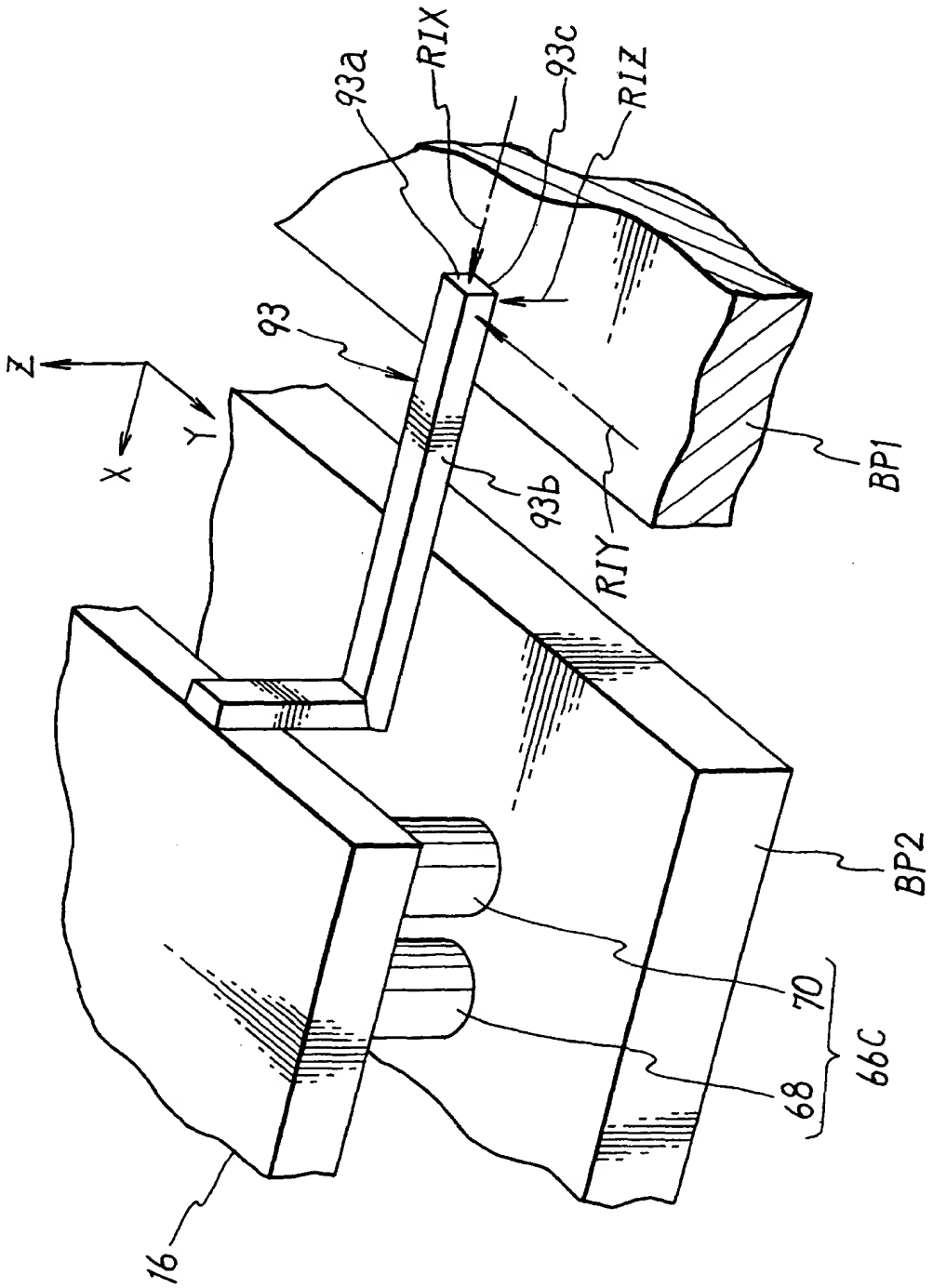
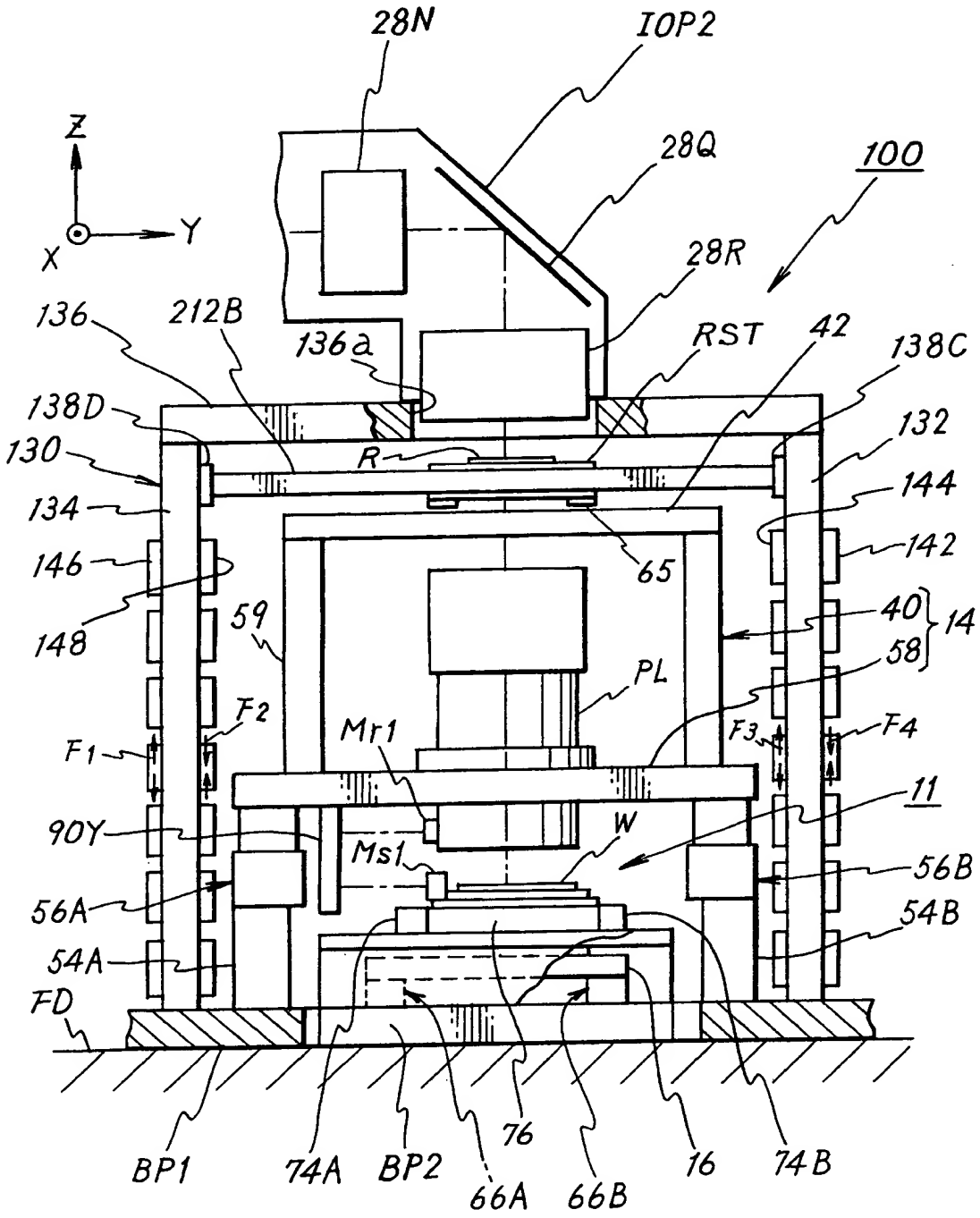


Fig. 5

F i g. 6


28N
IOP2
28Q
100
28R
Z
Y
X
136
212B
136a
RST
42
138C
138D
132
130
R
144
134
142
146
65
148
59
40
14
58
PL
F2
F3
F4
F1
Mr1
11
90Y
W
Ms1
56B
56A
54B
54A
FD
BP1
74A
BP2
76
66A
66B
16
74B

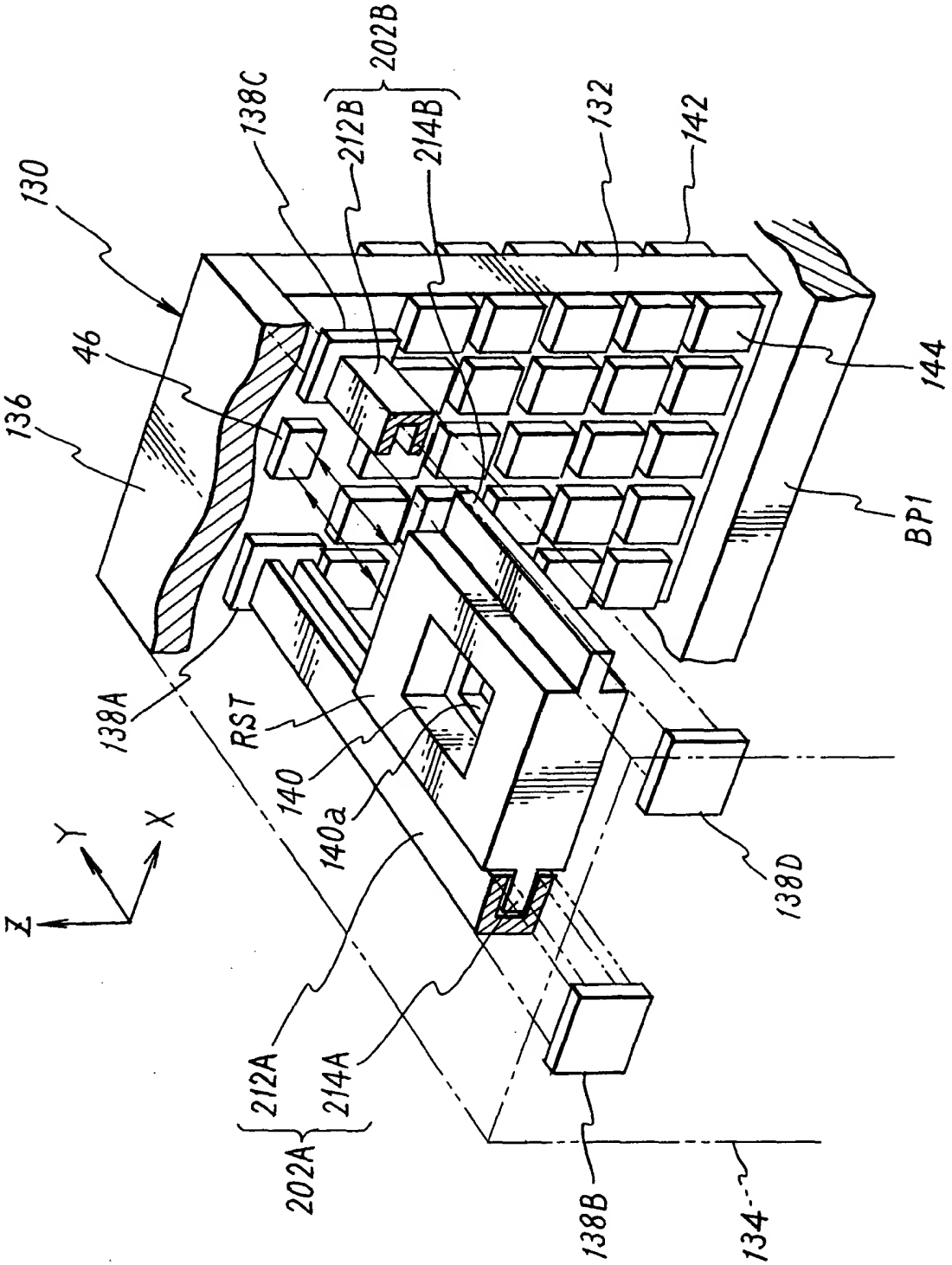

130
138C
212B
214B
202B
132
142
46
136
144
BP1
138A
RST
140
140a
138D
Y
X
Z
212A
214A
202A
138B
134

Fig. 7

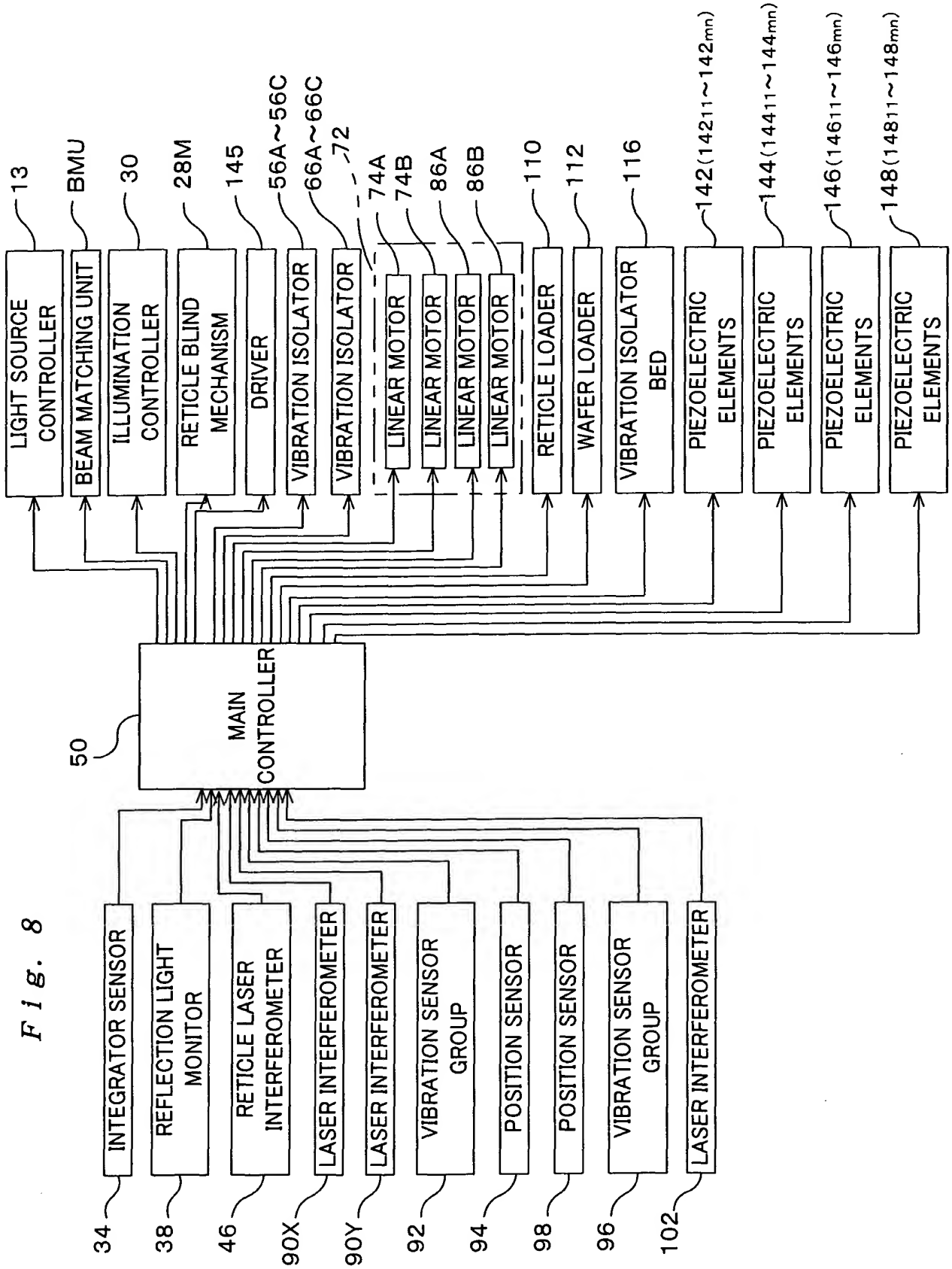

LIGHT SOURCE CONTROLLER
13
BEAM MATCHING UNIT
BMU
ILLUMINATION CONTROLLER
30
RETICLE BLIND MECHANISM
28M
DRIVER
145
VIBRATION ISOLATOR
56A~56C
VIBRATION ISOLATOR
66A~66C
VIBRATION ISOLATOR
72
LINEAR MOTOR
74A
LINEAR MOTOR
74B
LINEAR MOTOR
86A
LINEAR MOTOR
86B
RETICLE LOADER
110
WAFER LOADER
112
VIBRATION ISOLATOR
116
BED
PIEZOELECTRIC ELEMENTS
142(14211~142mn)
PIEZOELECTRIC ELEMENTS
144(14411~144mn)
PIEZOELECTRIC ELEMENTS
146(14611~146mn)
PIEZOELECTRIC ELEMENTS
148(14811~148mn)
MAIN CONTROLLER
50
INTEGRATOR SENSOR
34
REFLECTION LIGHT MONITOR
38
RETICLE LASER INTERFEROMETER
46
LASER INTERFEROMETER
90X
LASER INTERFEROMETER
90Y
VIBRATION SENSOR GROUP
92
POSITION SENSOR
94
POSITION SENSOR
98
VIBRATION SENSOR GROUP
96
LASER INTERFEROMETER
102

Fig. 8

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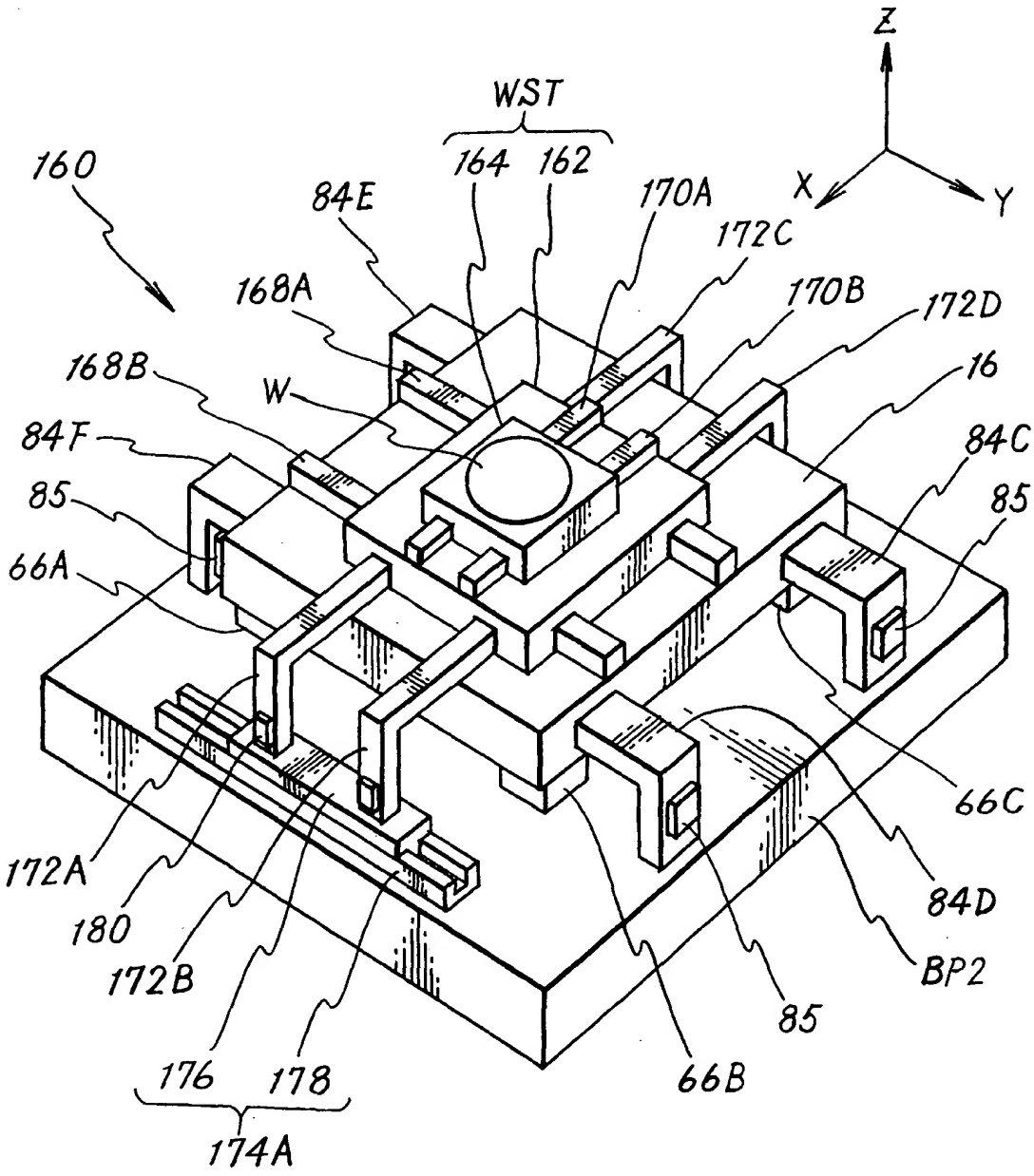
Fig. 9


Z
WST
164
162
160
84E
170A
X
Y
172C
168A
170B
172D
168B
W
16
84F
84C
85
85
66A
66C
172A
84D
180
172B
BP2
85
176
178
66B
174A

10/13

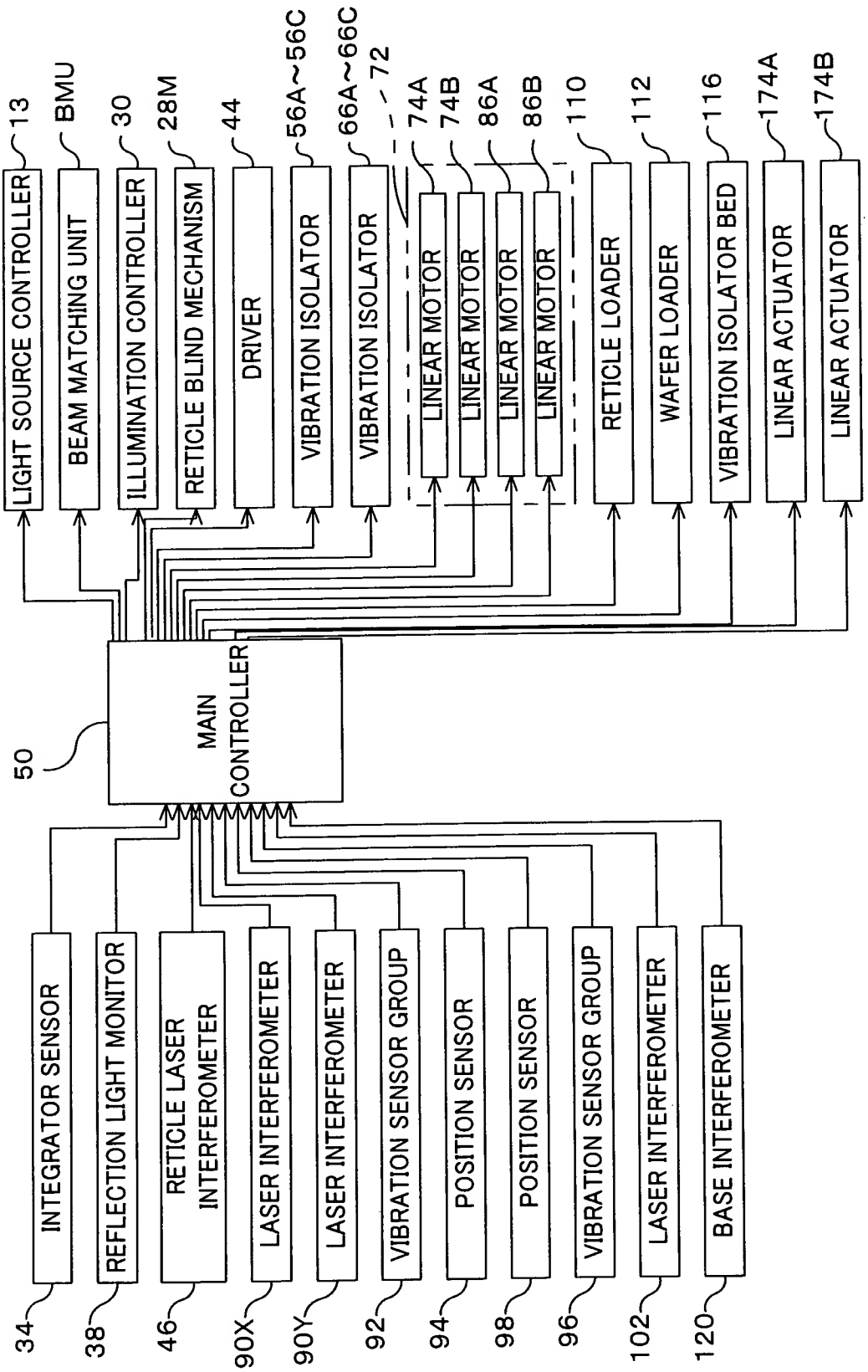

LIGHT SOURCE CONTROLLER
13
BEAM MATCHING UNIT
BMU
ILLUMINATION CONTROLLER
30
RETICLE BLIND MECHANISM
28M
DRIVER
44
VIBRATION ISOLATOR
56A~56C
VIBRATION ISOLATOR
66A~66C
72
LINEAR MOTOR
74A
LINEAR MOTOR
74B
LINEAR MOTOR
86A
LINEAR MOTOR
86B
RETICLE LOADER
110
WAFER LOADER
112
VIBRATION ISOLATOR BED
116
LINEAR ACTUATOR
174A
LINEAR ACTUATOR
174B
MAIN CONTROLLER
50
INTEGRATOR SENSOR
34
REFLECTION LIGHT MONITOR
38
RETICLE LASER INTERFEROMETER
46
LASER INTERFEROMETER
90X
LASER INTERFEROMETER
90Y
VIBRATION SENSOR GROUP
92
POSITION SENSOR
94
POSITION SENSOR
98
VIBRATION SENSOR GROUP
96
LASER INTERFEROMETER
102
BASE INTERFEROMETER
120

Fig. 10

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Fig. 11

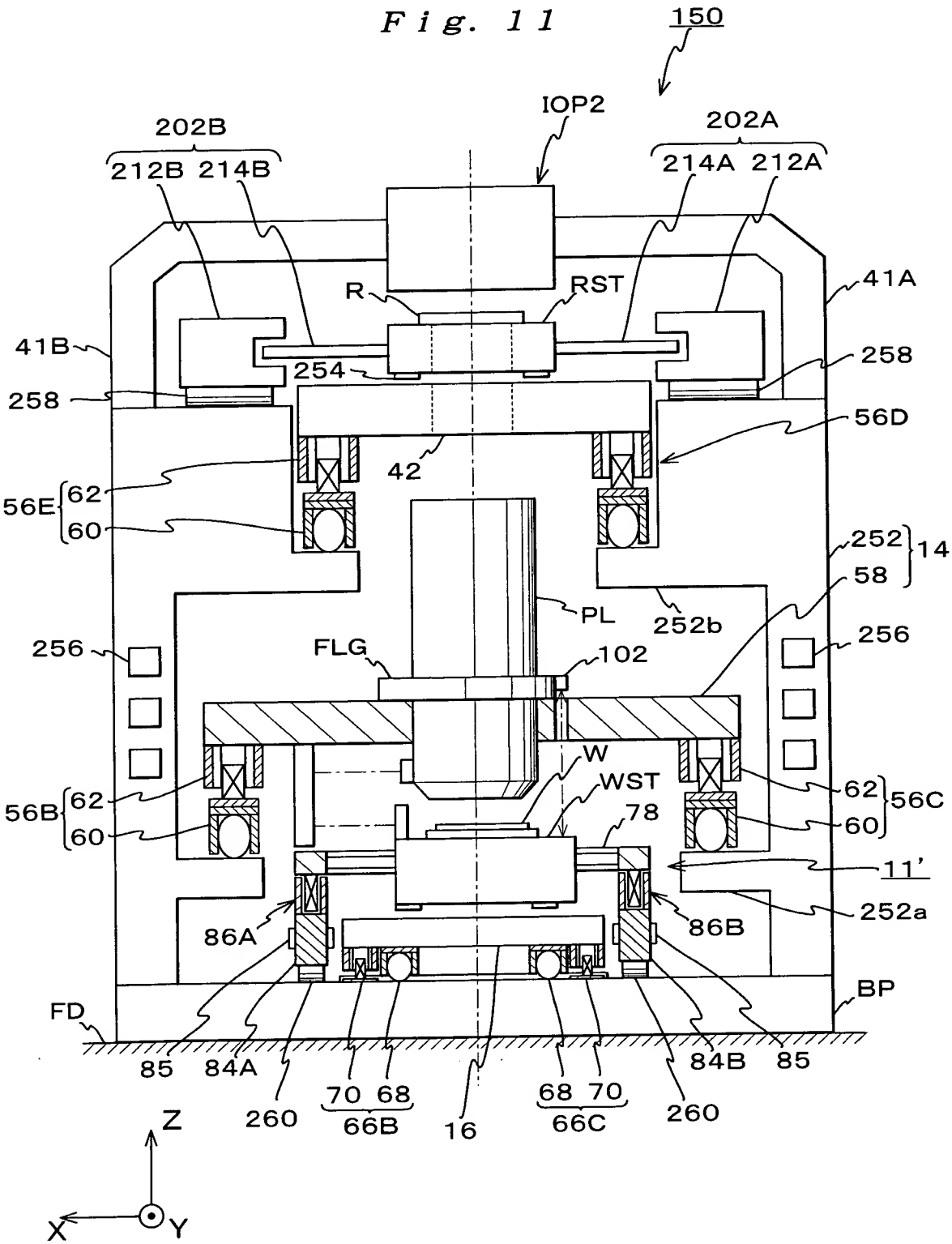


Fig. 12

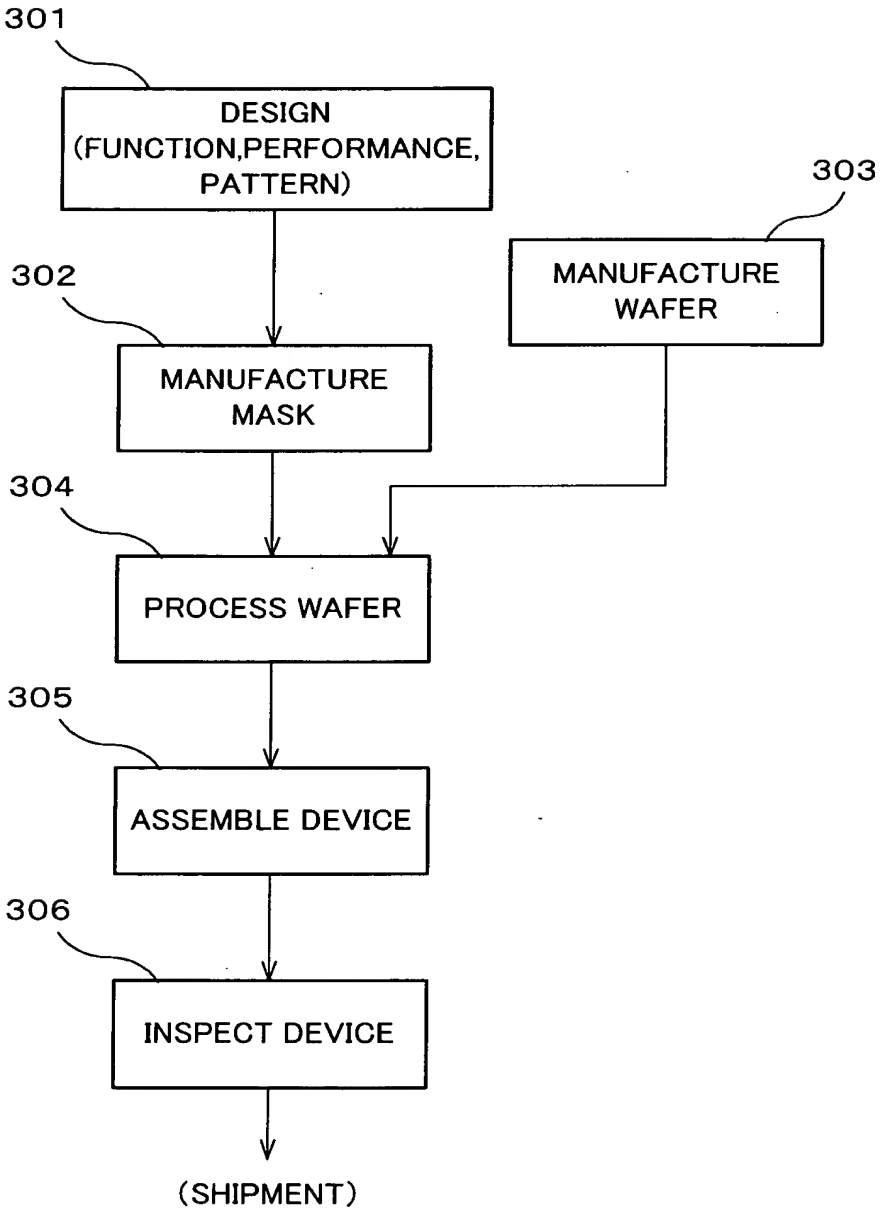
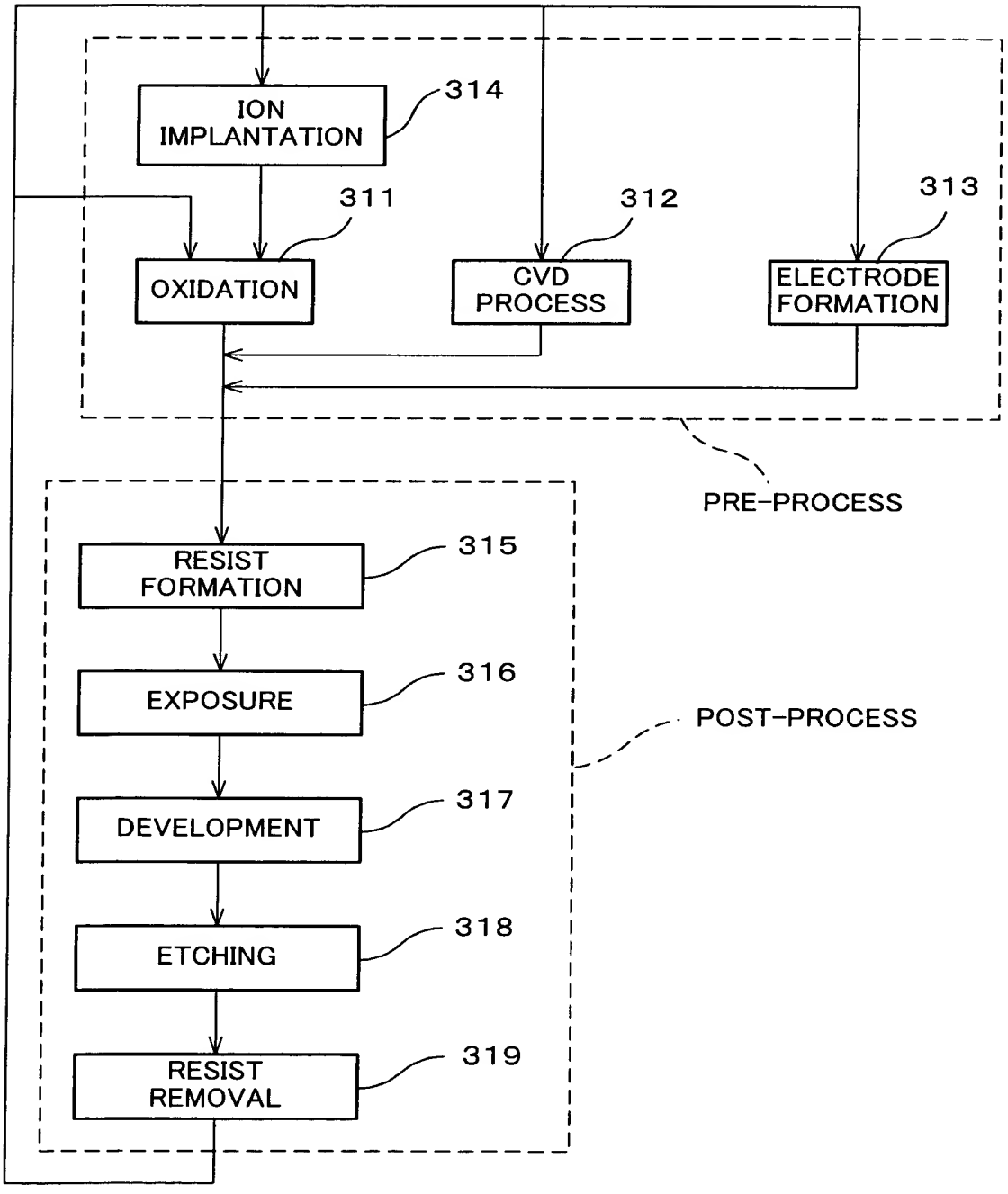

301
DESIGN (FUNCTION,PERFORMANCE, PATTERN)
303
MANUFACTURE WAFER
302
MANUFACTURE MASK
304
PROCESS WAFER
305
ASSEMBLE DEVICE
306
INSPECT DEVICE
(SHIPMENT)

Fig. 13


ION IMPLANTATION
314
311
312
313
OXIDATION
CVD PROCESS
ELECTRODE FORMATION
PRE-PROCESS
RESIST FORMATION
315
EXPOSURE
316
POST-PROCESS
DEVELOPMENT
317
ETCHING
318
RESIST REMOVAL
319